



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Ed  
10/4/02  
8/B  
(NE)

Applicant(s): MATSUI

Atty. Dkt.: 01-099

Serial No.: 09/709,454

Group Art Unit: 3723

Filed: Nov. 13, 2000

Examiner: SHAKERI, H.

Title: METHOD AND APPARATUS FOR  
MECHANOCHEMICAL  
POLISHING

Assistant Commissioner for Patents  
Washington, D.C. 20231

Date: September 30, 2002

Do not  
enter  
10/07/02

**CERTIFICATE OF HAND DELIVERY**

I hereby certify that this correspondence is being hand delivered to and deposited with the USPTO at the Customer Service Window, Office of Initial Patent Examination, Crystal Plaza Building 2, Room 1B03, 2011 South Clark Place, Arlington, VA 22202 on Sept. 30 2002.

Typed Name: DAVID G. POSZ

Signature: David G. Posz

**AMENDMENT**

Sir:

In response to the Office Action mailed May 16, 2002, please enter the following amendments and consider the appended remarks.

**IN THE CLAIMS**

Please cancel claims 45, 46, 66 and 72 - 73 without prejudice.

Please amend the claims as follows:

RECEIVED  
OCT 03 2002  
TECHNOLOGY CENTER R3700

44. (Once Amended) A method for mechanochemical polishing, comprising:  
preparing a chemical solution that includes hydrogen peroxide water and abrasive grains  
made of chromium (III) oxide;  
polishing a surface of a semiconductor wafer by mechanochemical polishing using the  
chemical solution and a polishing cloth; and

Sub C17  
B1